

TI-35669

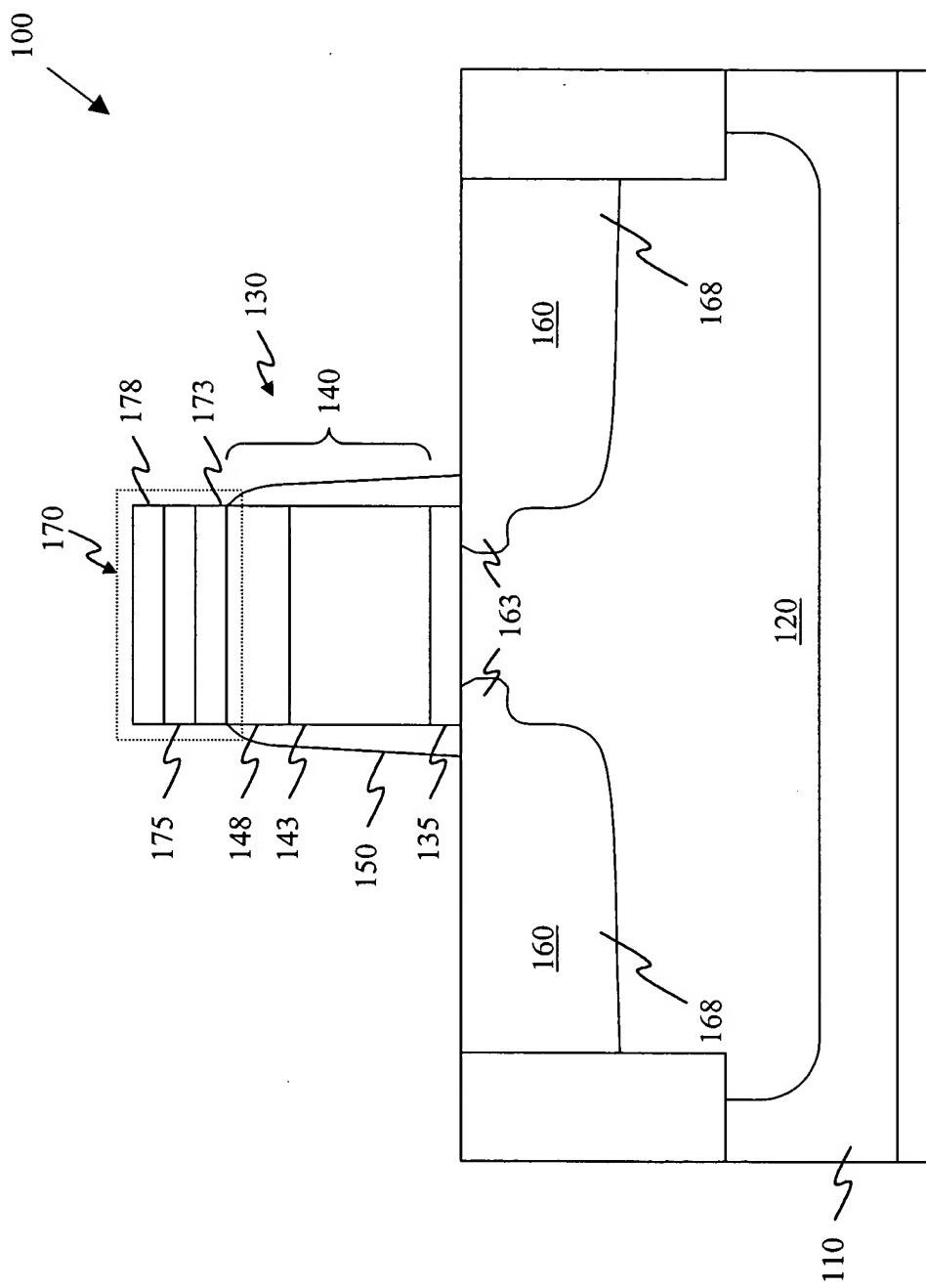


FIGURE 1A

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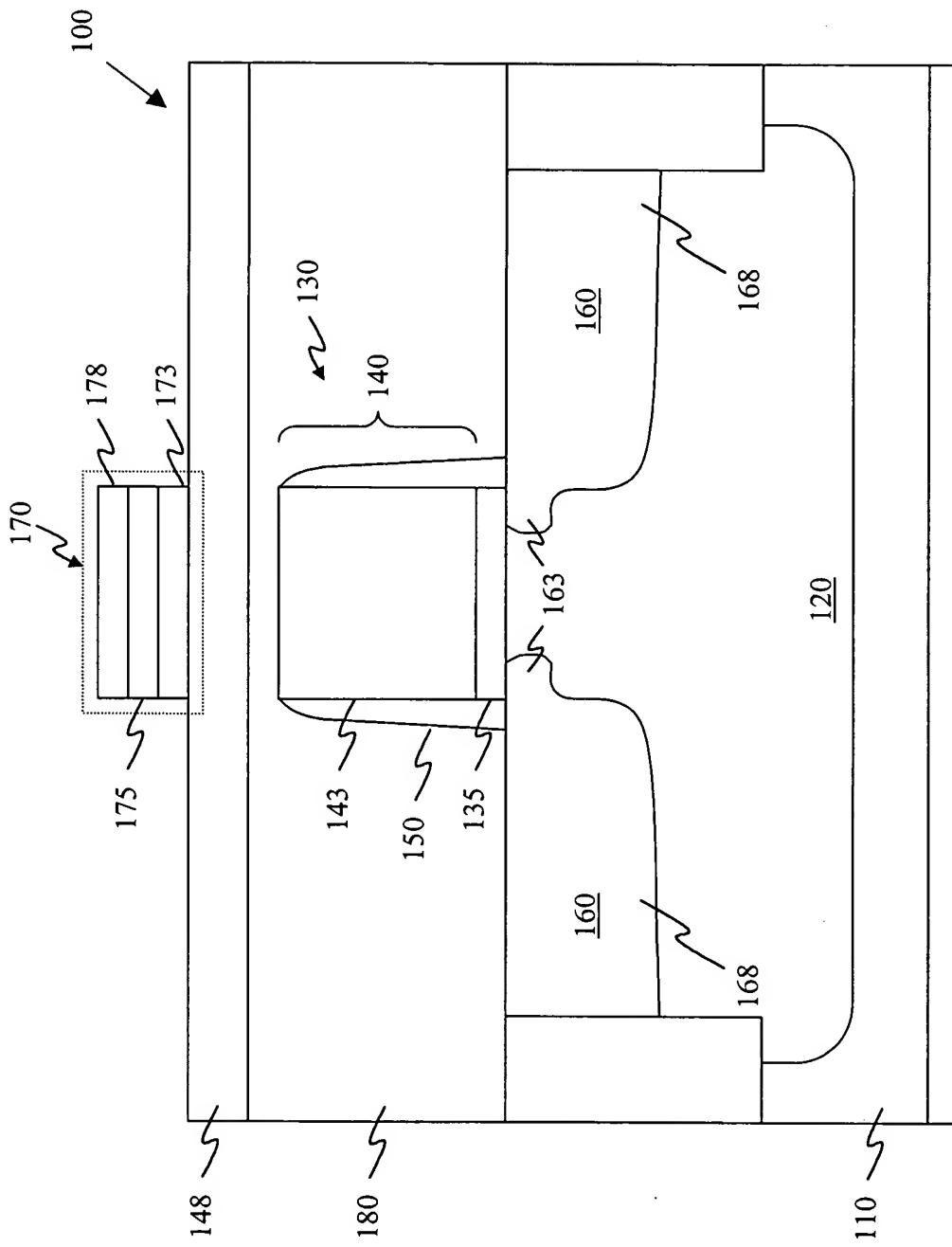


FIGURE 1B

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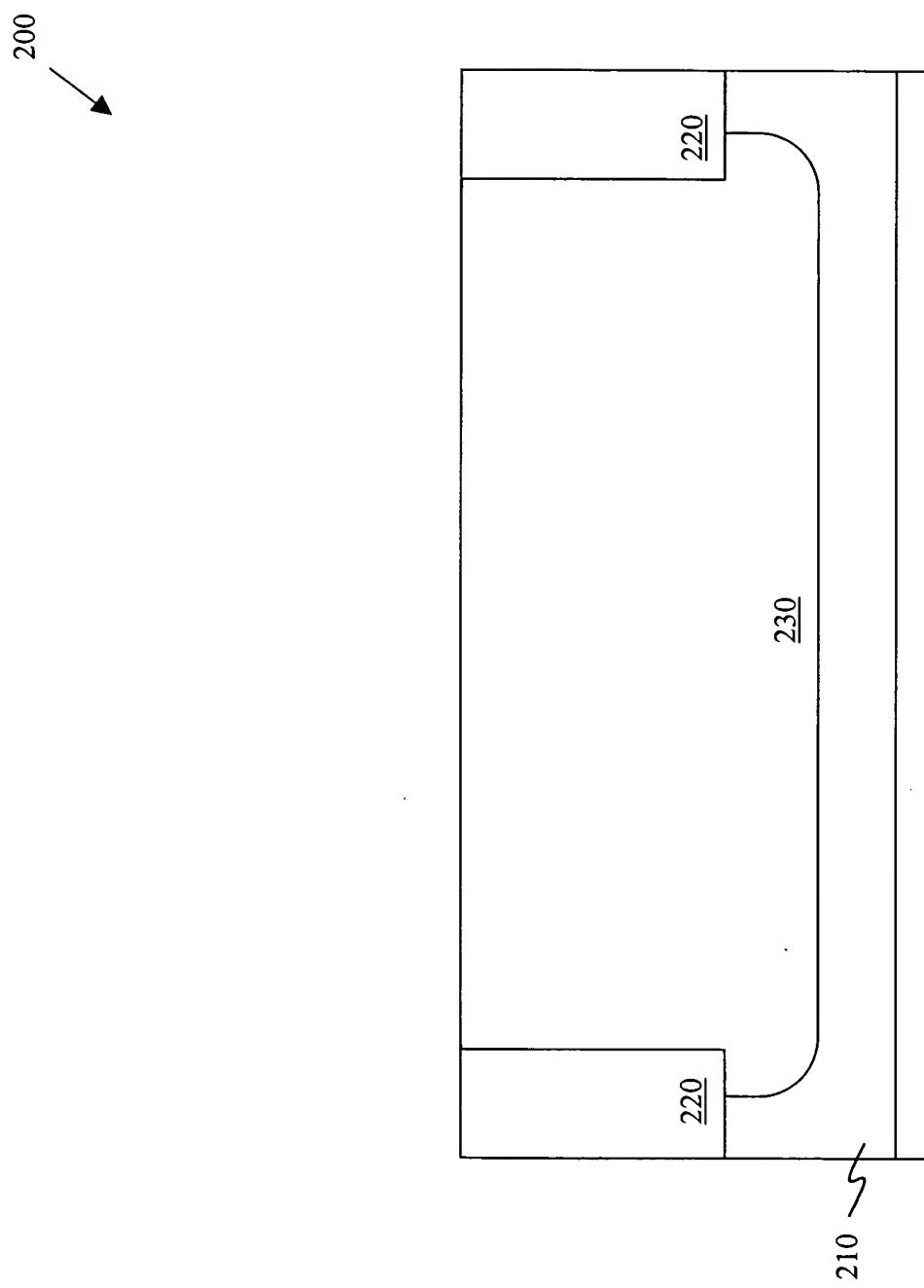


FIGURE 2

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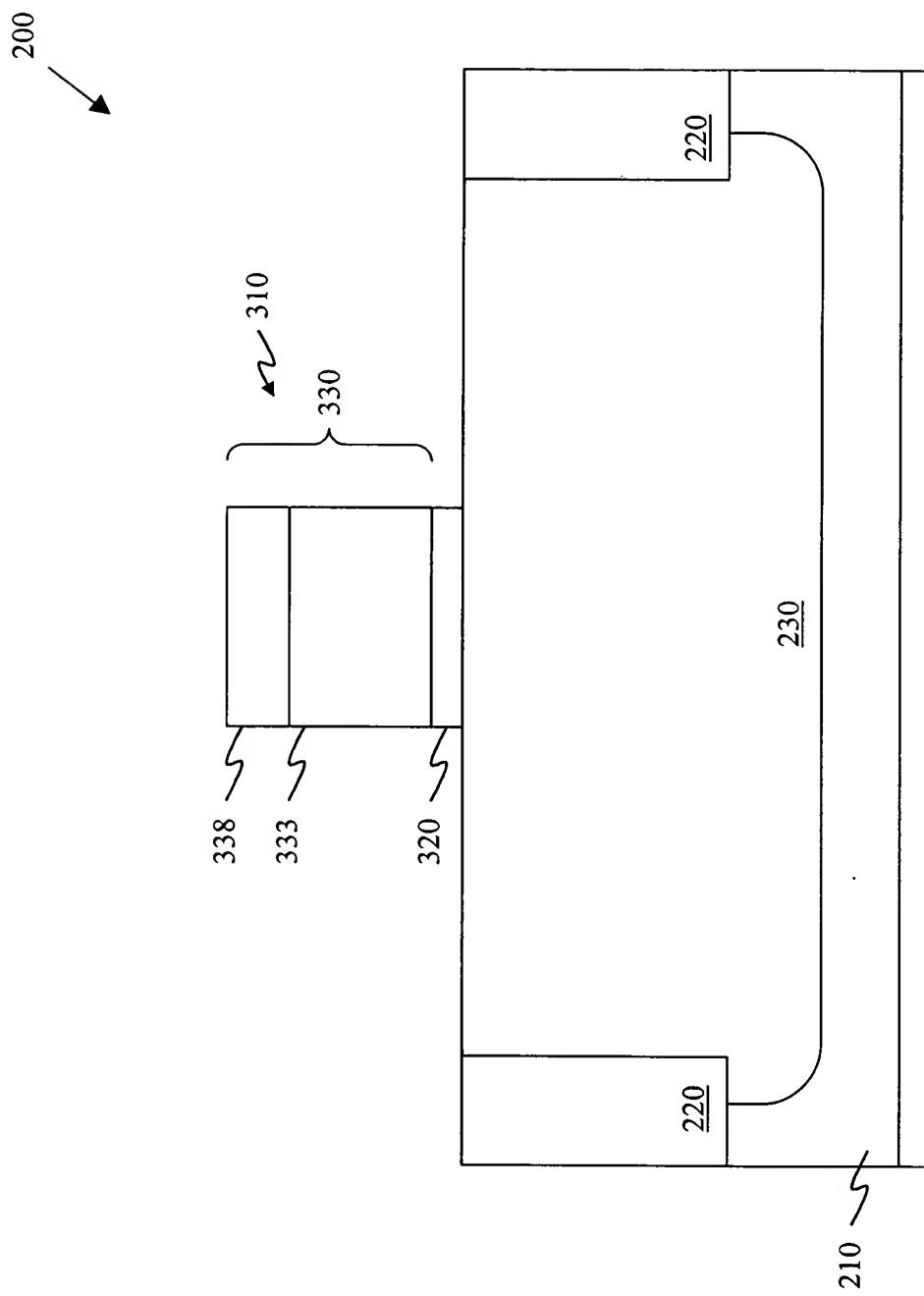


FIGURE 3

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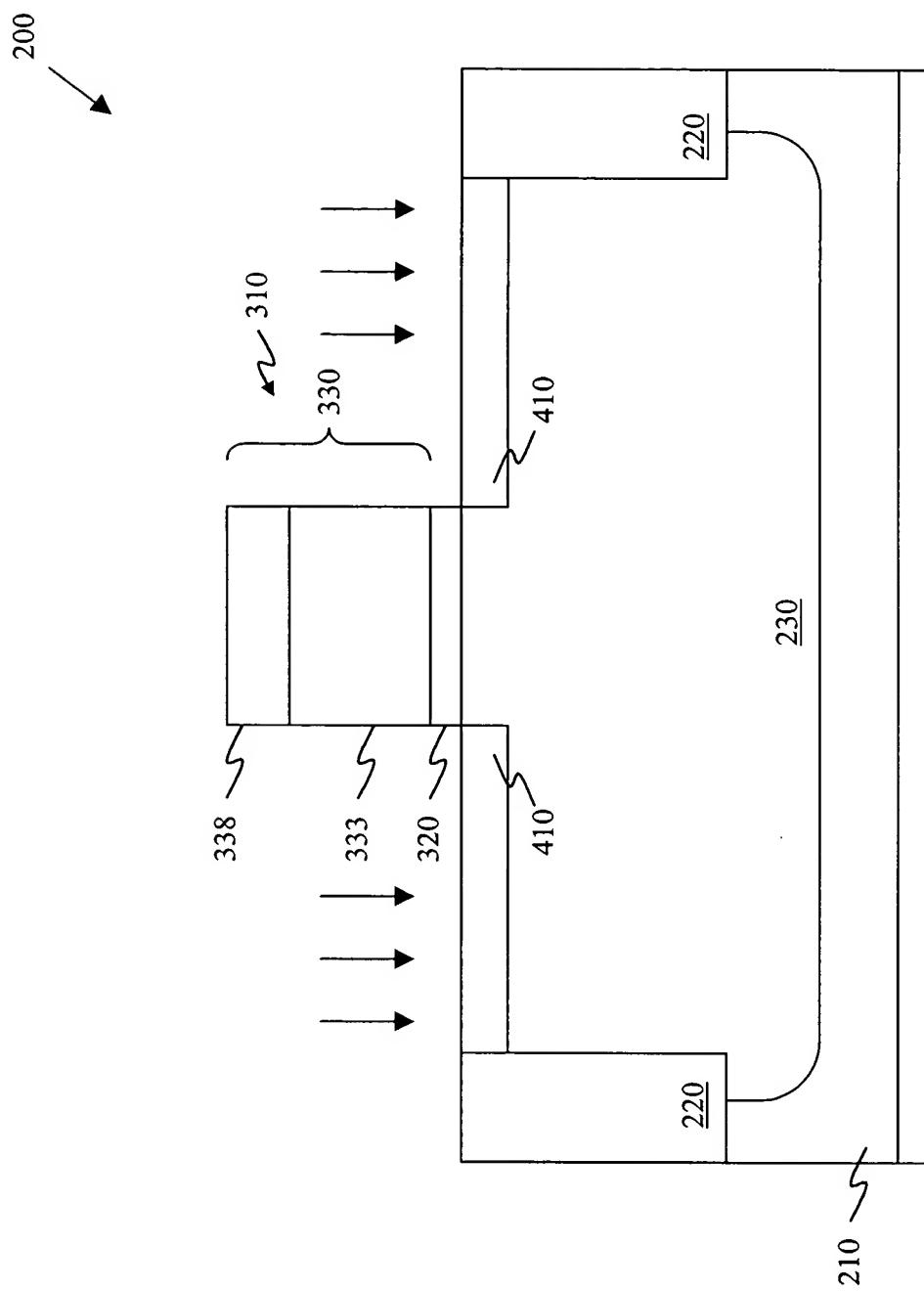


FIGURE 4

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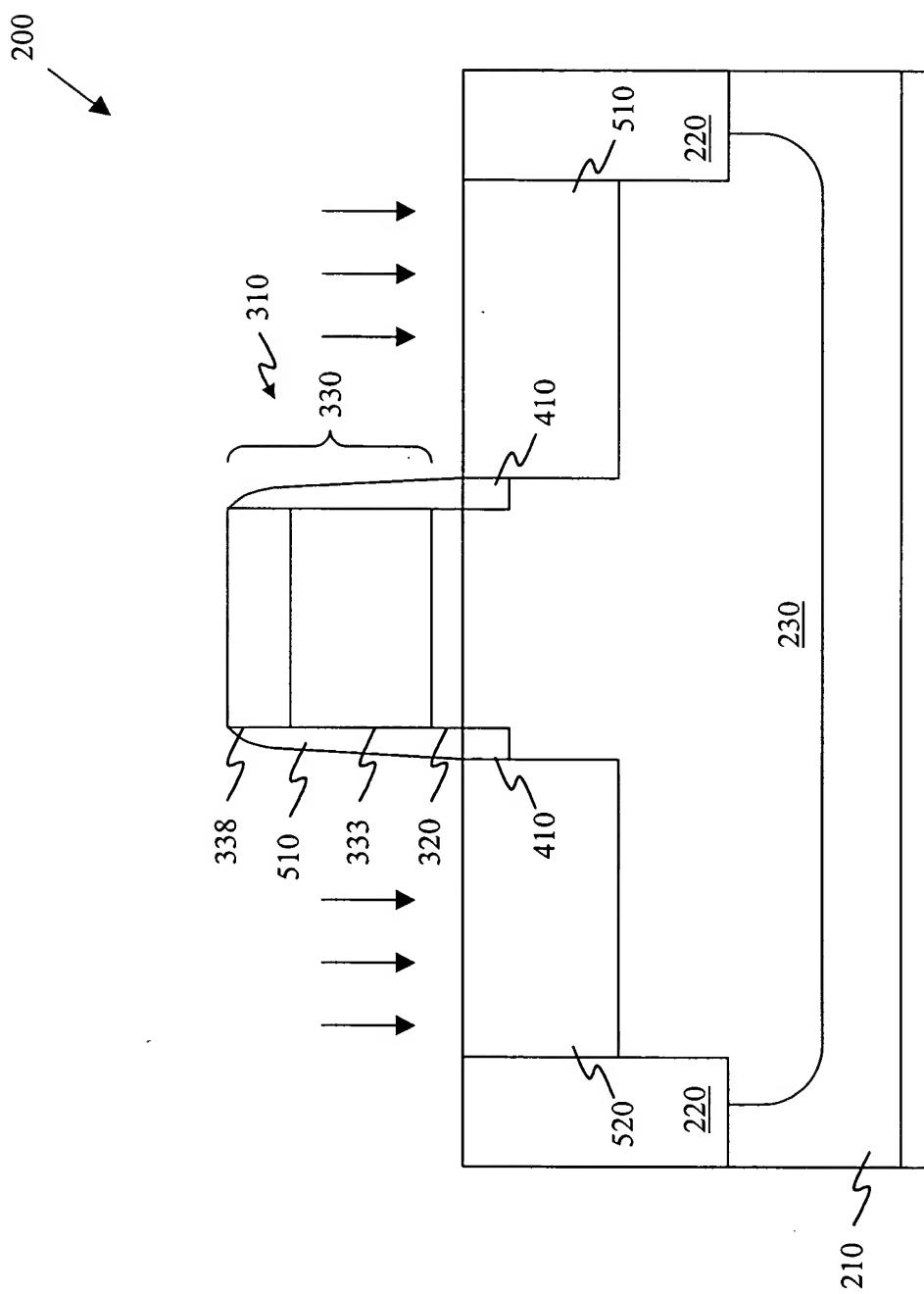


FIGURE 5

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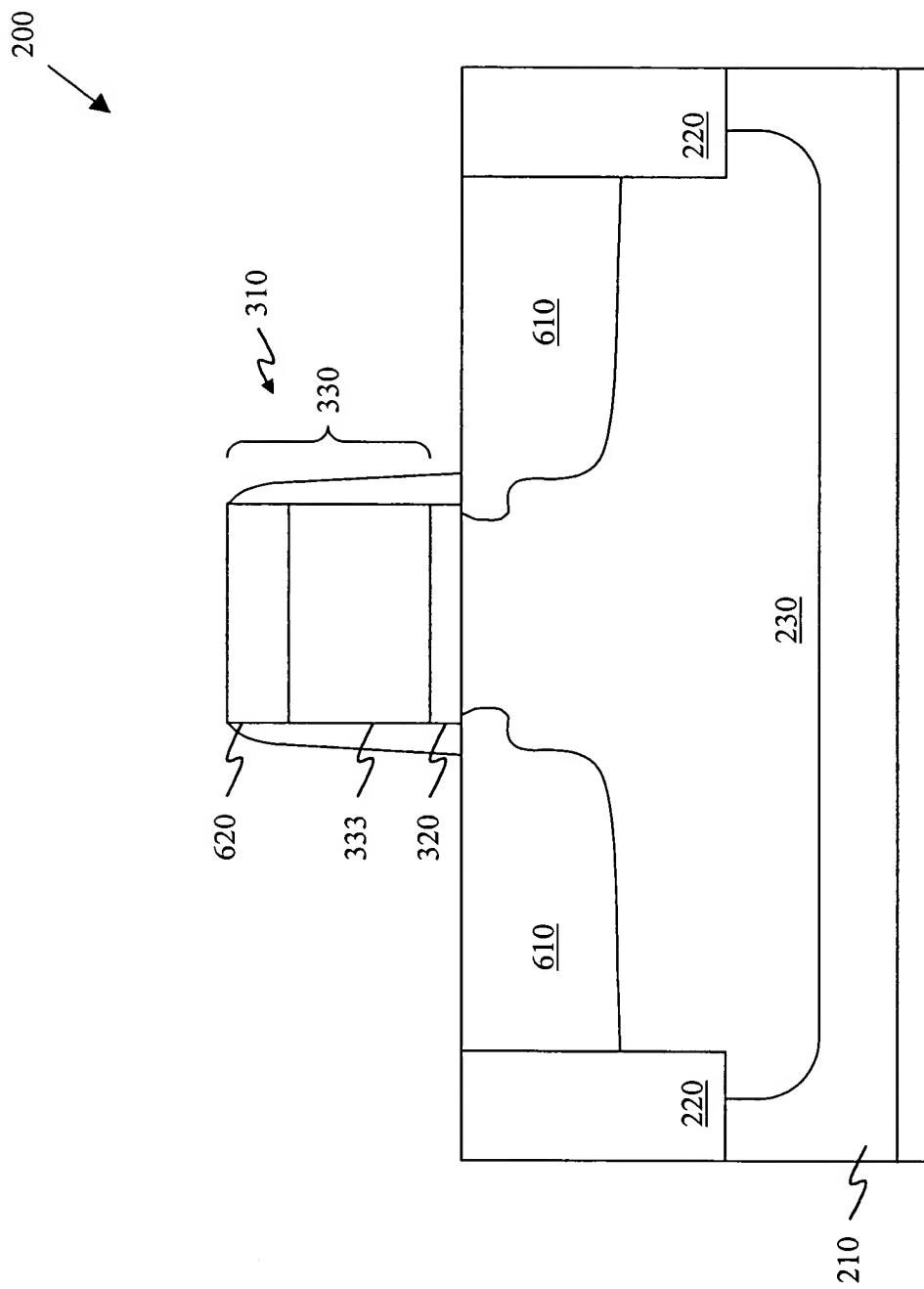


FIGURE 6

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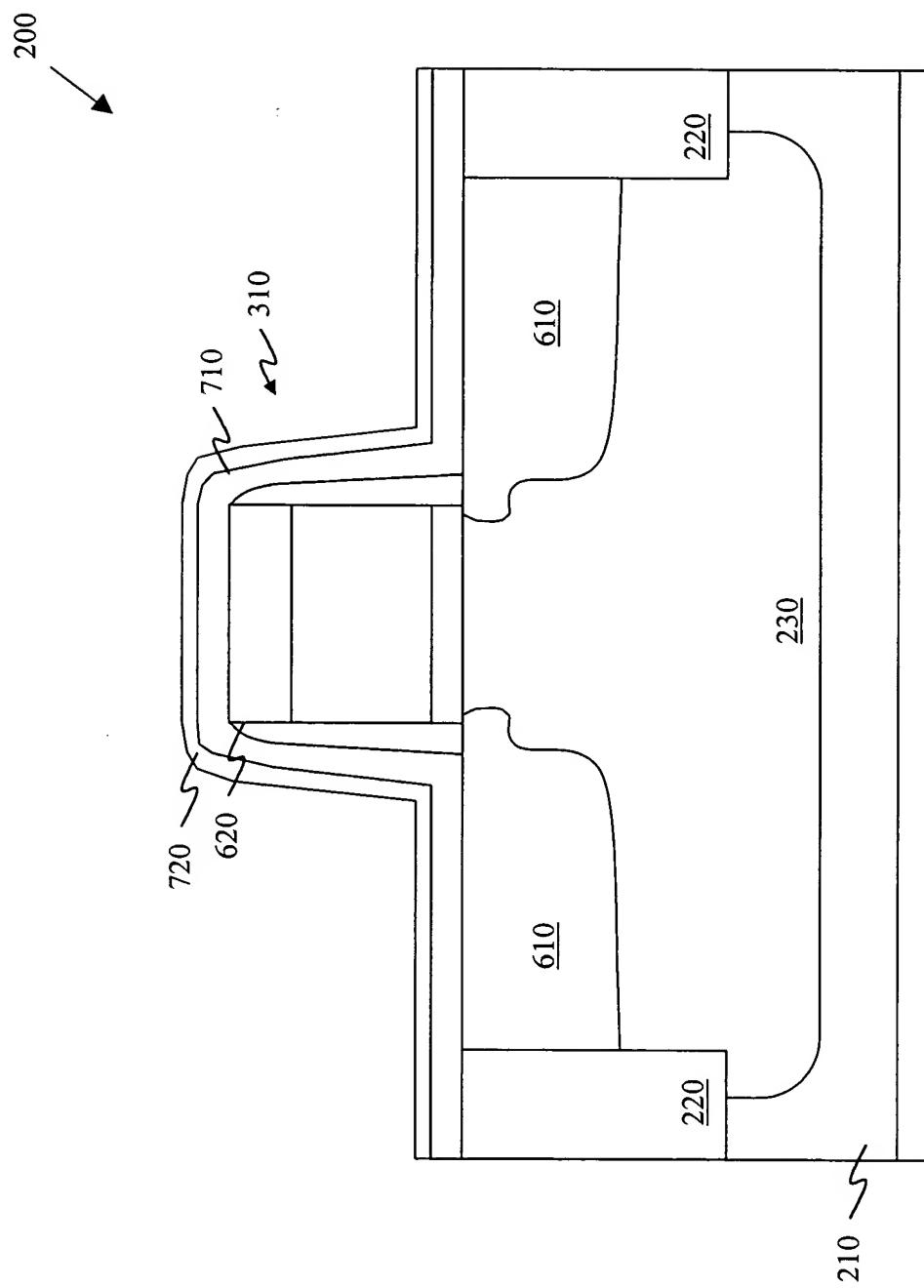


FIGURE 7

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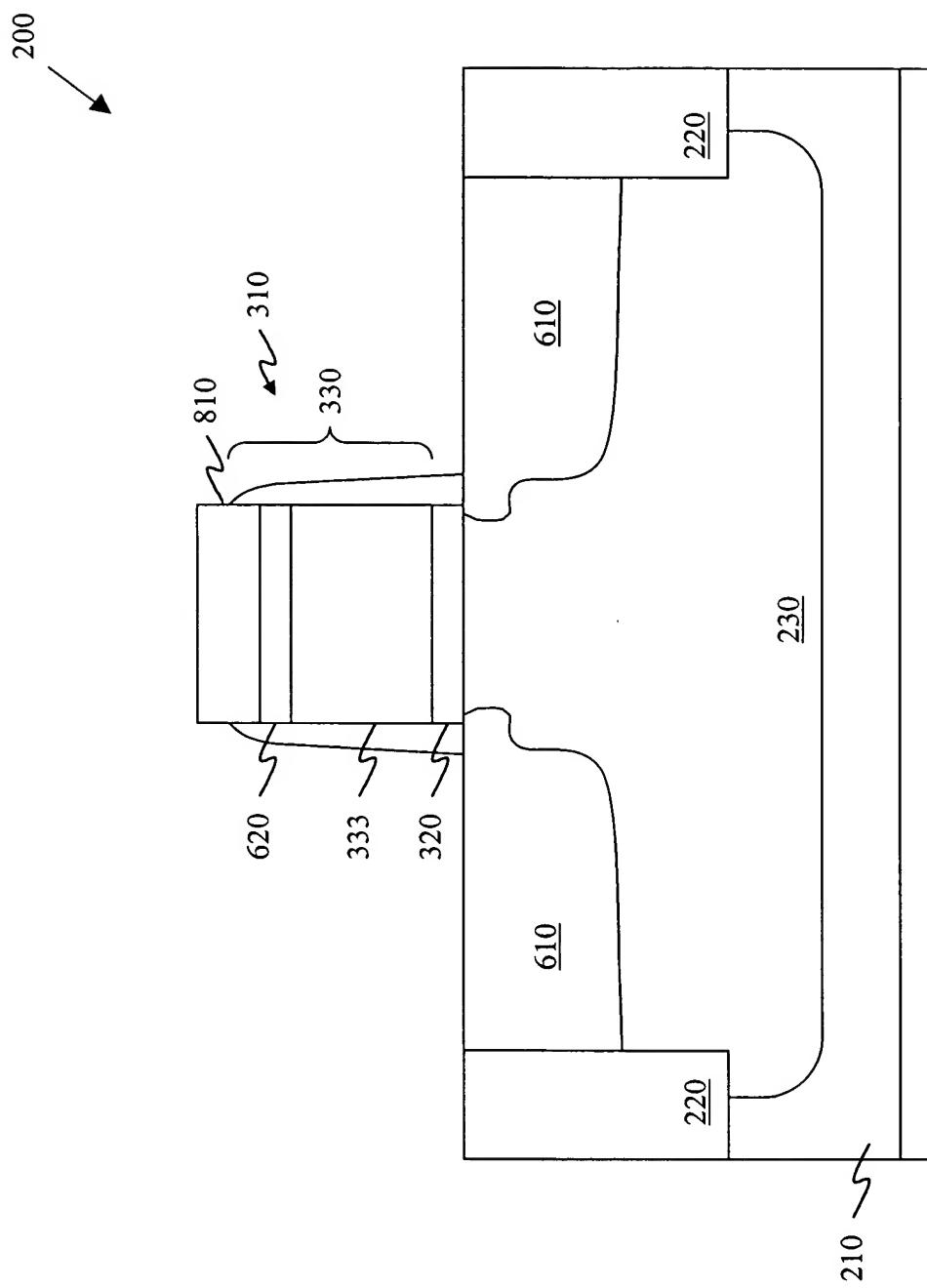


FIGURE 8

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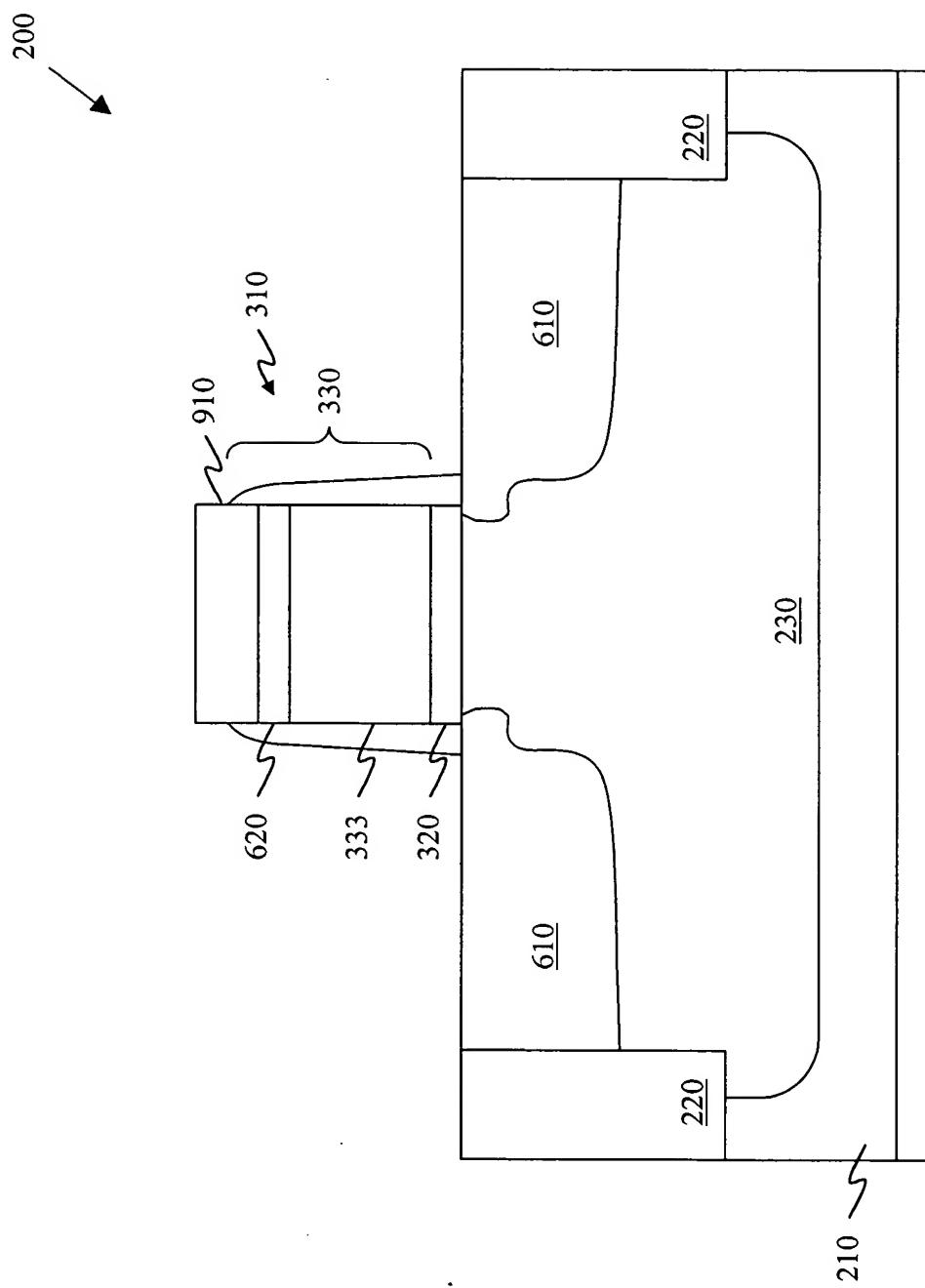


FIGURE 9

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1000  
→

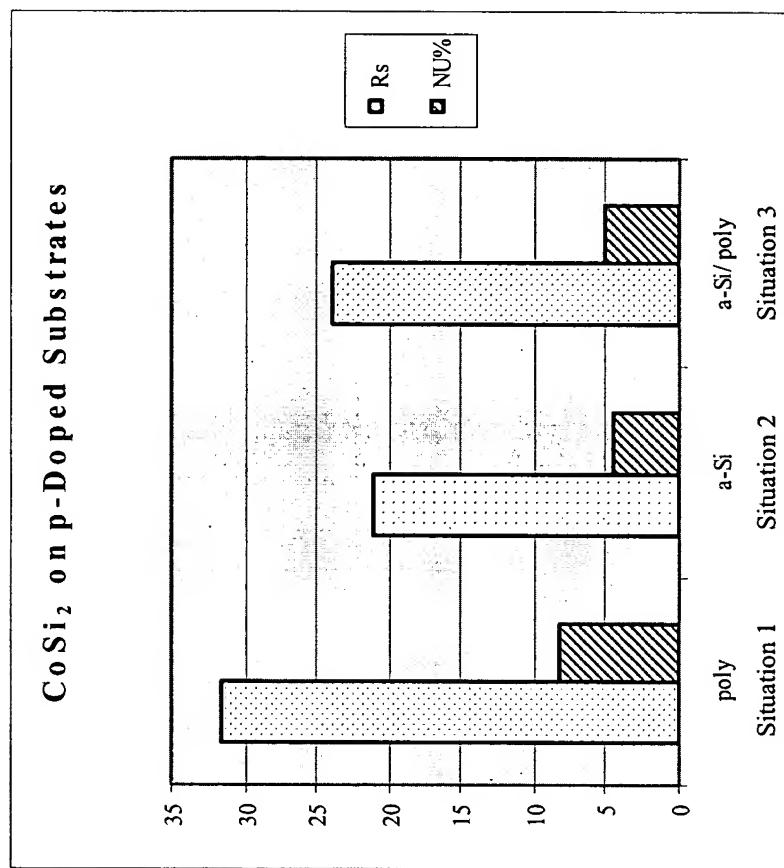


FIGURE 10

1100  
→

## Surface Roughness by AFM

Situation	RMS[nm]	test1	test2	test3
1	<b>3.000</b>	3.116	2.976	2.909
2	<b>1.621</b>	1.558	1.659	1.645
3	<b>2.064</b>	1.904	2.387	1.901

- Situation 1 – CoSi<sub>2</sub> formed on poly-Si
- Situation 2 – CoSi<sub>2</sub> formed on a-Si
- Situation 3 – CoSi<sub>2</sub> formed on a-Si/poly stack

FIGURE 11

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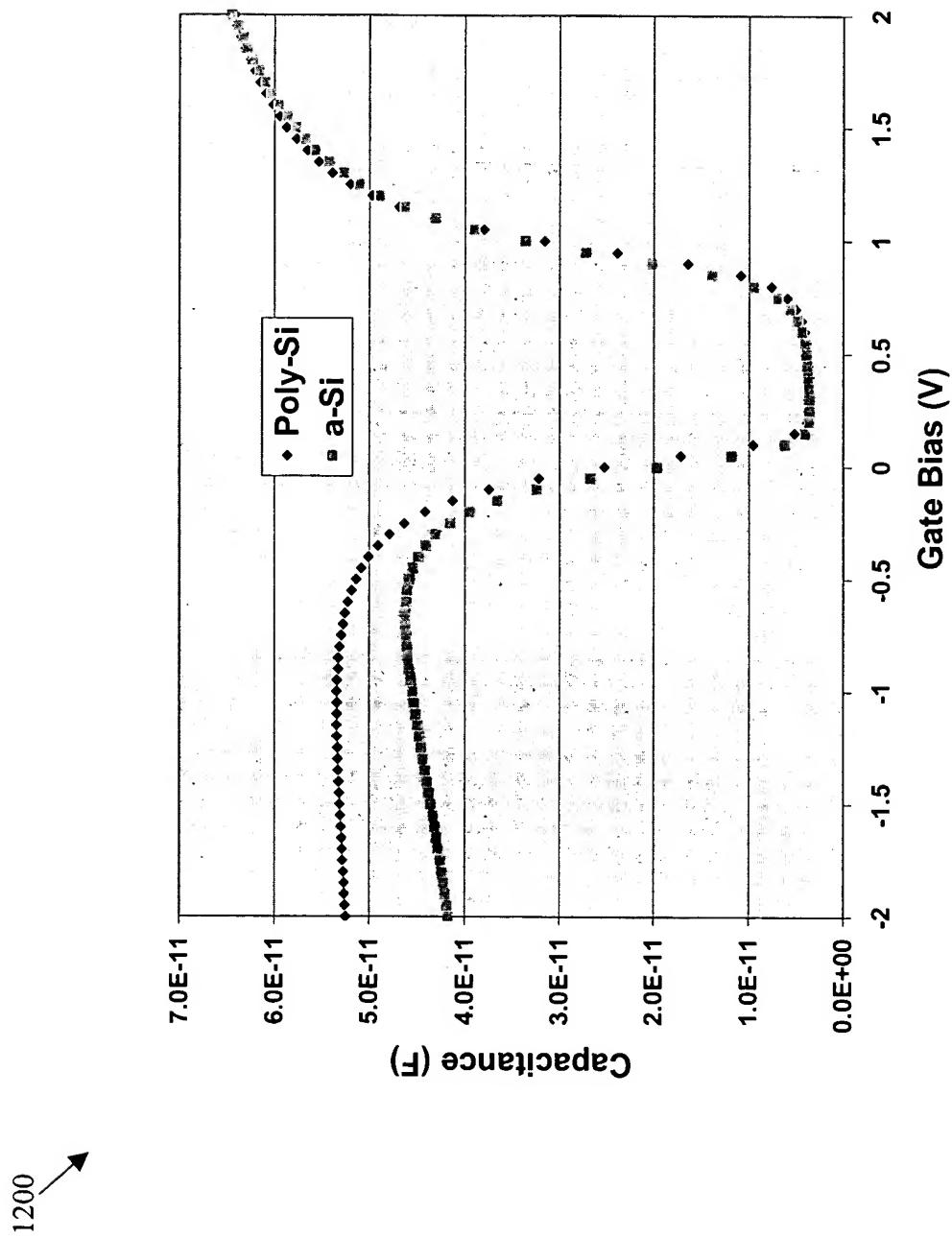


FIGURE 12

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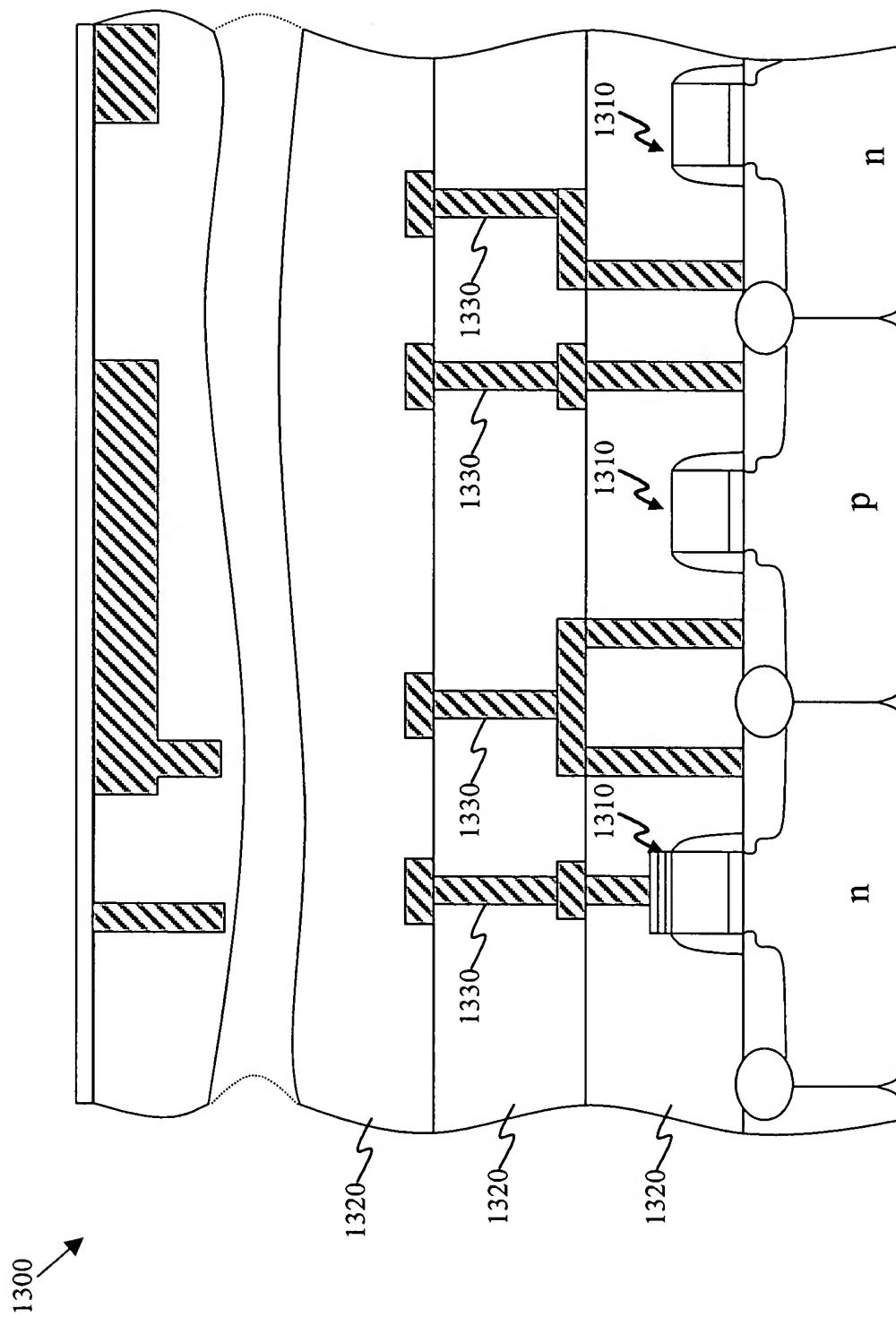


FIGURE 13